

Electronic Acknowledgement Receipt

EFS ID:	1274250
Application Number:	10666354
International Application Number:	
Confirmation Number:	8188
Title of Invention:	Two step post-deposition treatment of ILD layer for a lower dielectric constant and improved mechanical properties
First Named Inventor/Applicant Name:	Hui-Lin Chang
Customer Number:	42717
Filer:	David M. Odell/Denise Wilson
Filer Authorized By:	David M. Odell
Attorney Docket Number:	TS02-1079
Receipt Date:	25-OCT-2006
Filing Date:	19-SEP-2003
Time Stamp:	18:27:36
Application Type:	Utility

Payment information:

Submitted with Payment	no
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File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part /.zip	Pages (if appl.)
1	Amendment - After Non-Final Rejection	Response.pdf	450387	no	12

Warnings:

Information:	
Total Files Size (in bytes):	450387
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<p>New Applications Under 35 U.S.C. 111 If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.</p>	
<p>National Stage of an International Application under 35 U.S.C. 371 If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.</p>	